

Resource Summary Report

Generated by [NIF](#) on Sep 11, 2026

JEOL: JBX-9500FS Electron Beam Lithography System

RRID:SCR_020171

Type: Tool

Proper Citation

JEOL: JBX-9500FS Electron Beam Lithography System (RRID:SCR_020171)

Resource Information

URL: <https://www.jeolusa.com/PRODUCTS/Photomask-Direct-Write-Lithography/Electron-Beam-Lithography/JBX-9500FS>

Proper Citation: JEOL: JBX-9500FS Electron Beam Lithography System (RRID:SCR_020171)

Description: Electron beam lithography system that is versatile in its applications from basic research of elements to test production of optical elements to research and development for masks for high accelerating voltage exposure.

Resource Type: instrument resource

Keywords: Jeol, JEOL, Electron Beam Lithography System, Instrument Equipment, USEDit,

Availability: Commercially available

Resource Name: JEOL: JBX-9500FS Electron Beam Lithography System

Resource ID: SCR_020171

Alternate IDs: Model_Number_JBX_9500FS

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260905T132910+0000

Ratings and Alerts

No rating or validation information has been found for JEOL: JBX-9500FS Electron Beam Lithography System.

No alerts have been found for JEOL: JBX-9500FS Electron Beam Lithography System.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.